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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of: **Akira MATSUDA et al.**

Art Unit: **1794**

Application Number: **10/719,020**

Examiner: **Michael E. Lavilla**

Filed: **November 24, 2003**

Confirmation Number: **9168**

For: **PLATING BATH FOR FORMING THIN RESISTANCE LAYER, METHOD OF FORMATION OF RESISTANCE LAYER, CONDUCTIVE BASE WITH RESISTANCE LAYER, AND CIRCUIT BOARD MATERIAL WITH RESISTANCE LAYER**

Attorney Docket Number: **032130**

Customer Number: **38834**

INFORMATION DISCLOSURE STATEMENT
UNDER 37 C.F.R. §1.97(c)(1)/(e)(1)

Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

June 25, 2008

Sir:

Applicants direct the attention of the Patent and Trademark Office to the documents listed on the attached Form PTO/SB/08. A copy of each non - U.S. document is attached.

Documents 1, 2, 4, and 5 were cited in an Office Action for a corresponding Chinese application. A copy of the Office Action is also enclosed.

Document 3 is a patent family member of document 5 and not directly cited in the Office Action.

This Information Disclosure Statement (IDS) is being submitted after issuance of a first official action on the merits and expiration of the three month period following the filing date or the entry of the national stage for the above-captioned application, but prior to issuance of either a final official action or a Notice of Allowance.

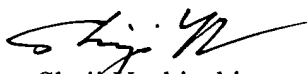
Application No.: 10/719,020
Art Unit: 1794

Information Disclosure Statement under 1.97(c)(1)
Attorney Docket No.: 032130

The undersigned hereby certifies that each item of information contained in the IDS was first cited in any communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of the IDS. A copy of the foreign communication citing the documents is attached.

If there are any fees due in connection with the filing of this paper, please charge Deposit Account No. 50-2866.

Respectfully submitted,
WESTERMAN, HATTORI, DANIELS & ADRIAN, LLP



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Enclosures: Limited Recognition
PTO/SB/08
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